

Piezobirefringence above the fundamental edge in Si

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We report measurements of stress-induced birefringence in silicon in a spectral region (1.65 to 3.4 eV) where the material is opaque. A new technique that employs Raman scattering is used to extend the range of previous measurements performed in the transparent region below 1.2 eV. Theoretical fits to the data are made by considering the contributions to piezobirefringence due to the E_1 , $E_1 + \Delta_1$, and E_2 transitions under uniaxial stresses along the [001] and [111] directions.

I. INTRODUCTION

Stress-induced birefringence in cubic semiconductors that are optically isotropic if unstressed has been studied in a variety of materials^{1,2} near and below the fundamental edge. Conventional techniques¹⁻³ employ transmission of light through the sample, and are consequently limited to a frequency region where the material is transparent. In the opaque region above the fundamental edge limited success has been reported in obtaining relative values of the piezo-optical constants in silicon using data obtained from piezoreflectance.^{4,5} These difficulties have been overcome with a new technique that employs Raman scattering⁶: using this method we have already reported⁶ measurements of the magnitudes of the piezo-optical constants $\pi_{11} - \pi_{12}$ and π_{44} at 1.92 eV, well above the fundamental gap of 1.1 eV. In this paper we present measurements of the piezo-optical constants in the energy range from 1.65 to 3.4 eV, a region easily accessible to conventional lasers.

Previous measurements¹ of piezobirefringence in silicon in the transparent region between 0.6 and 1.2 eV exhibit little dispersion near the fundamental edge. This is a consequence of the indirect nature of the fundamental edge in this material, which is too weak to contribute significantly to the real part of the dielectric constant. The present measurements approach the direct gap in Si (~3.3 eV) and show a strong dispersion near this gap similar to the results obtained for the direct gaps of Ge and GaAs.¹ We calculate the contribution to the piezobirefringence due to the E_1 , $E_1 + \Delta_1$ gaps, which provide the main dispersive terms around 3.3 eV, while the E_2 gap at 4.4 eV contributes only a slowly varying term in the region of interest. The contribution from the E'_0 gap, also near 3.3 eV, is neglected owing to its small oscillator strength. The calculations are compared with experiment, and good agreement is obtained using the deformation potentials of the E_1 , $E_1 + \Delta_1$ transitions and the magnitude of

the contribution from the E_2 gap as adjustable parameters. The deformation potentials used agree with previous measurements of these quantities to within a factor of 2, which may be a result of the simple model we have used to fit the experimental data.

Pure Si (carrier concentration 10^{13} cm⁻³) was used in our experiments in order to eliminate any free-carrier effects. All experiments were performed at room temperature. Uniaxial stress was applied along the [100] and [110] directions to determine $\pi_{11} - \pi_{12}$ and π_{44} , respectively.

The experimental details are described in Sec. II; Section III presents the experimental results and their analysis, while Sec. IV provides a discussion and theoretical interpretation of the experimental results. Section V reviews the main conclusions of the work.

II. EXPERIMENTAL DETAILS

Raman measurements were performed in the back-scattering geometry standard for opaque materials. Ar⁺ and Kr⁺ lasers were used to obtain the exciting radiation, the polarization of which was turned with a polarization rotator to obtain light linearly polarized at 45° to the stress axis. The scattered light was analyzed with a sheet polarizer. Standard polarization rotators and analysers could not be used in the ultraviolet at 3638 Å; therefore, a combination of a 3600-Å quarter-wave plate and a Babinet compensator were used to rotate the polarization of the incident light, and a Glan Thomson prism was used as an analyzer. The detection system consisted of a double monochromator with holographic gratings, a cooled photomultiplier equipped with photon-counting electronics, and a multichannel analyzer for data storage. The stress apparatus equipped with digital readout has been described previously in the literature.⁷ Compressive stresses up to a maximum of 22 kbar were applied to the samples that had a typical cross section of

$1.3 \times 1.3 \text{ mm}^2$. The samples were cut and x-ray oriented to within 1° , and the face used for scattering was polished with $0.3\text{-}\mu\text{m}$ alumina and polish etched with Syton⁸ for 10 min.

III. EXPERIMENTAL RESULTS AND ANALYSIS

When a uniaxial stress is applied to a cubic crystal, the crystal becomes birefringent, and a phase difference is induced between the components of light polarized parallel and perpendicular to the stress axis. This stress-induced birefringence causes a depolarization of the incident and scattered radiation within the crystal in a manner similar to that observed in light-scattering experiments in birefringent materials.⁹ This depolarization is used to measure the stress-induced birefringence coefficients (piezo-optical constants). The method⁶ is as follows: Raman scattering is observed in a back-scattering geometry standard for opaque materials. A Raman-active structure and a sample orientation are chosen such that in a configuration with light polarized and analyzed at 45° to the stress direction, the structure under consideration (a phonon or an overtone) has zero Raman intensity at zero stress. When a stress is applied, the intensity increases from zero due to the stress-induced birefringence which changes the polarization of the incident and scattered fields within the crystal. Likewise the same phonon or overtone in a different polarization configuration (also at 45° to the stress direction) that has maximum Raman intensity at zero stress, decreases in intensity on the application of stress. The ratio of the two intensities as a function of stress is used to determine the absolute values of the piezo-optical constants $\pi_{11} - \pi_{12}$ and π_{44} . No information is obtained on the hydrostatic piezo-optical constant $\pi_{11} + 2\pi_{12}$ since the birefringence is induced by the shear component of the stress.

Details of the theoretical analysis have been published elsewhere.⁶ A brief description follows. To describe the scattering geometry, a coordinate system is chosen such that the \hat{z} axis is perpendicular to the scattering face. The stress direction is chosen to be $(1/\sqrt{2})(\hat{x} + \hat{y})$, while $(1/\sqrt{2})(\hat{x} - \hat{y})$ is perpendicular to both \hat{z} and the stress direction. The stress is chosen along either [100] or [110] crystal directions, \hat{z} being along either [001] or $[1\bar{1}0]$ for each stress direction. On the application of stress, a phase difference ϕ is induced between the electric vectors of the radiation polarized parallel and perpendicular to the stress, for both the incident and scattered light.

For incident or scattered polarizations of light along \hat{x} or \hat{y} (at 45° to the stress axis) the elec-

tric vectors will be

$$\begin{aligned}\hat{e}_x &= \frac{1}{2}[(\hat{x} + \hat{y}) + (\hat{x} - \hat{y})e^{i\phi}], \\ \hat{e}_y &= \frac{1}{2}[(\hat{x} + \hat{y}) - (\hat{x} - \hat{y})e^{i\phi}],\end{aligned}\quad (1)$$

respectively, where ϕ is the phase difference at a depth l within the crystal, and is given by

$$\phi(2\pi/\lambda)(n_{\parallel} - n_{\perp})l, \quad (2)$$

where n_{\parallel} and n_{\perp} are the refractive indices for light polarized parallel and perpendicular to the stress direction; the difference $n_{\parallel} - n_{\perp}$ is linear in stress and depends on the sample orientation. λ is the wavelength of the incident or scattered radiation, which are taken to be equal owing to the small frequency of the phonon as compared with that of the incident or scattered radiation.

At a depth l within the crystal, the intensity of the incident light is attenuated by a factor $e^{-\alpha_i l}$, where α_i is the absorption coefficient at the incident frequency. The scattered light is similarly attenuated with an absorption coefficient α_s . Using the electric vectors in Eq. (1) and the Raman tensor R_j of the phonon (j labels degenerate phonons) the total intensity due to a phonon observed in a given polarization configuration, say $z(xx)\bar{z}$, can be calculated to be

$$I_{xx} = \int_0^{\infty} \sum_j |\hat{e}_x \cdot R_j \cdot \hat{e}_x|^2 e^{-(\alpha_i + \alpha_s)l} dl \quad (3a)$$

and similarly for the $z(xy)\bar{z}$ configuration

$$I_{xy} = \int_0^{\infty} \sum_j |\hat{e}_x \cdot R_j \cdot \hat{e}_y|^2 e^{-(\alpha_i + \alpha_s)l} dl, \quad (3b)$$

where factors common to Eqs. (3a) and (3b) have been dropped. The standard notation for scattering geometries is used, i.e., $z(xy)\bar{z}$ denotes that the incident and scattered wave vectors are along z and \bar{z} , while x and y denote the polarizations of the incident and scattered radiation, respectively.

The scattering face and stress direction are chosen such that one of the intensities I_{xx} or I_{xy} for the chosen phonon is zero and the other non-zero at zero stress. The intensity ratio $\beta = I_{xx}/I_{xy}$ or I_{xy}/I_{xx} is defined so that $\beta = 0$ at zero stress, and is obtained from Eqs. (3) as a function of stress. For a given sample orientation β is related through $n_{\parallel} - n_{\perp}$ to the piezo-optical constants. Several combinations of phonons and sample orientations can be used to determine the magnitude (not the sign) of $\pi_{11} - \pi_{12}$ and π_{44} . Six possible combinations are summarized in Table I. In each case we list the stress direction (column 1), scattering face (column 2), the electric vectors \hat{e}_x and \hat{e}_y in terms of the crystallographic directions (column 3), the intensities of the Γ_1 and $\Gamma_{25'}$ components of the Raman tensor seen in the (xx)

TABLE I. Six configurations for measuring the piezo-optical constants.

Case	(1) Stress direction	(2) Scattering- face \hat{z}	(3) Electric vectors of incident and scattered radiation \hat{e}_x \hat{e}_y		(4) Components of the Raman tensor in the $z(xx)\bar{z}$ and $z(xy)\bar{z}$ configurations ^a	(5) Phonon chosen and its symmetry	(6) Intensity ratio β given by	(7) Piezo-optical coefficient measured
(a)	[110]	[001]	[100]	[010]	Γ_1 $\Gamma_{25'}$	$O(\Gamma)$, $\Gamma_{25'}$	Eq. (4)	π_{44}
(b)	[001]	[100]	[110]	[1 $\bar{1}$ 0]	$\Gamma_1 + \Gamma_{25'}$ 0	2 TA(X), Γ_1	Eq. (5)	$\pi_{11} - \pi_{12}$
(c)	[111]	[1 $\bar{1}$ 0]	[001]	[110]	Γ_1 $\Gamma_{25'}$	$O(\Gamma)$, $\Gamma_{25'}$	Eq. (7)	π_{44}
(d)	[110]	[001]	[100]	[010]	Γ_1 $\Gamma_{25'}$	2 TA(X), Γ_1	Eq. (8)	π_{44}
(e)	[001]	[100]	[110]	[1 $\bar{1}$ 0]	$\Gamma_1 + \Gamma_{25'}$ 0	$O(\Gamma)$, $\Gamma_{25'}$	Eq. (9)	...
(f)	[110]	[1 $\bar{1}$ 0]	[11 $\sqrt{2}$]	[11 $\sqrt{2}$]	$\Gamma_1 + \frac{5}{4}\Gamma_{25'}$ $\frac{1}{4}\Gamma_{25'}$	2 TA(X), Γ_1	Eq. (10)	$\frac{1}{2}(\pi_{11} - \pi_{12} + \pi_{44})$

^a The Γ_{12} component has been omitted since both the $O(\Gamma)$ and 2TA(X) phonons have negligible intensity in this component.

and (xy) polarization configurations at zero stress (column 4), the phonon chosen and its symmetry [the zone-center phonon $O(\Gamma)$ has $\Gamma_{25'}$ symmetry, while the second-order acoustic phonon 2TA(X) has mainly Γ_1 symmetry] (column 5), the intensity ratio β for the chosen phonon as a function of stress (column 6), and the piezo-optical constant measured in that configuration (column 7). The direction of applied stress and the face used determines which piezo-optical constant is measured,¹⁰ independent of the phonon used. The functional form of β , however, is dependent on both the sample orientation and the phonon symmetry. Of the six cases listed in Table I, we chose two simple cases (a) and (b) to measure $\pi_{11} - \pi_{12}$ and π_{44} as a function of incident frequency. The four others were used as confirming checks.

Careful alignment of the polarizer and analyzer at zero stress was necessary in order to obtain the best extinction ratio between the nonallowed and allowed configurations for the chosen phonon. Although one expects $\beta = 0$ at zero stress, small misalignments of the sample and possible leakage through the polarization rotator and analyzer are believed to be the main cause of the small intensity seen in a forbidden configuration at zero stress. This leakage was observed to increase with increasing exciting energy, varying after the background was subtracted, from 1% at 1.65 eV to 5% at 3.4 eV for the zone-center phonon, with

similar numbers for 2TA(X) scattering. Part of this leakage is, of course, due to the finite angle of incidence ($\leq 30^\circ$) used in the experiments, which in itself rotates the direction of polarization in the unstressed crystal by $\sim 2^\circ$. We corrected for this effect by slightly rotating the polarizer and analyzer to make sure that we were at the maximum or minimum of scattered intensity, as required. The increase in "leakage" with increasing photon energy mentioned above may be due to the increasing extinction coefficient which results, for non-normal incidence, in elliptically polarized light inside the unstressed sample and thus makes extinction by readjusting polarizers impossible.

Case (a). Stress $\bar{X} \parallel [110]$, scattering from a (001) face produced by the zone-center optical phonon $O(\Gamma)$ of $\Gamma_{25'}$ (T_{2g}) symmetry at a frequency of 520 cm^{-1} . It has zero intensity in the $z(xx)\bar{z}$, and a maximum intensity in the $z(xy)\bar{z}$ configuration at zero stress where \hat{x} is [100] and \hat{y} is [010] (Table I).

The intensity ratio is therefore defined as $\beta = I_{xx}/I_{xy}$, which is zero at zero stress. Upon the application of stress, the intensity of the zone-center phonon in the (xx) configuration grows at the expense of that in the (xy) configuration. In Fig. 1 we plot the data obtained for the zone-center phonon in the (xx) and (xy) configurations at zero and 20 kbar for an exciting wavelength of 7525 \AA . The intensity of the (xx) mode is 1%

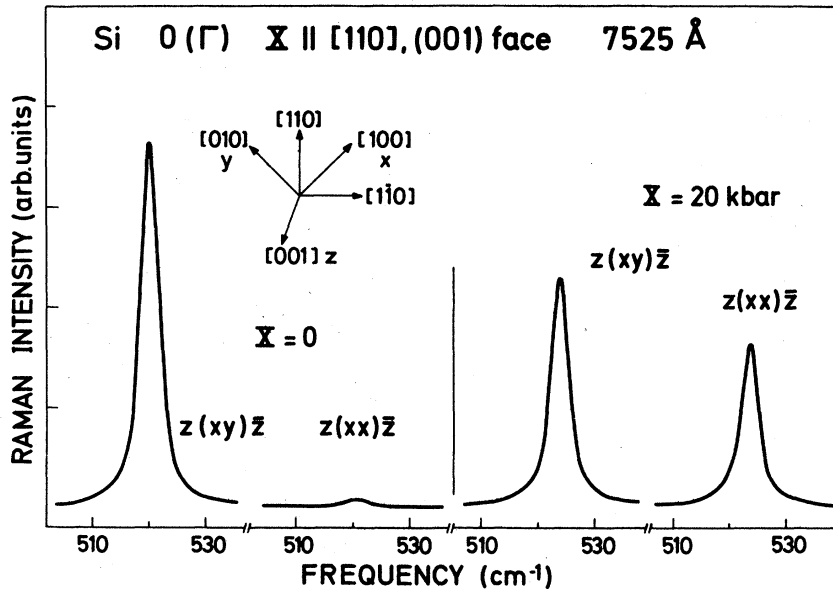


FIG. 1. Birefringence-induced changes in the intensity of the optical phonon for stress $\bar{X} \parallel [110]$, measured with an exciting wavelength of 7525 Å. The intensity ratio β grows from 1% at zero stress to about 70% at 20 kbar.

that of the (xy) mode at zero stress, and the ratio grows to about 70% at 20 kbar. The calculated intensity ratio as a function of stress, obtained by substituting the appropriate Raman tensor¹¹ and integrating Eq. (3), is

$$\beta = \frac{I_{xx}}{I_{xy}} = \frac{1}{1 + 1/2(AX)^2}, \quad (4a)$$

where X is the applied stress and

$$A = \pi n_0^3 \pi_{44} / \lambda (\alpha_i + \alpha_s) \quad (4b)$$

is obtained by substituting the relation for $n_{\parallel} - n_{\perp}$ for this sample orientation¹⁰ in Eq. (2),

$$n_{\parallel} - n_{\perp} = -\frac{1}{2} n_0^3 \pi_{44} X, \quad (4c)$$

where X is negative for the compressive stresses used in our experiments, and n_0 is the refractive index at zero stress.

In Fig. 2 we plot the intensity ratio β versus stress X for several exciting wavelengths. The solid lines are fits to experimental data using Eq. (4a). The best fits were achieved by shifting the zero on the β axis by a small constant to take care of the leakage at zero stress. We note in Fig. 2 that the variation of β with stress depends strongly on the exciting frequency. The largest change in β with stress occurs at the longest wavelength, 7525 Å, where the penetration depth $[\frac{1}{2}(\alpha_i + \alpha_s)]^{-1}$ is the largest (approximately 7×10^4 Å), while the smallest change is observed at 3638 Å, where the penetration depth is about 125 Å. From the best fits to the data we obtain the parameter A and hence the magnitude of π_{44} for each wavelength. The values found are listed in Table II.

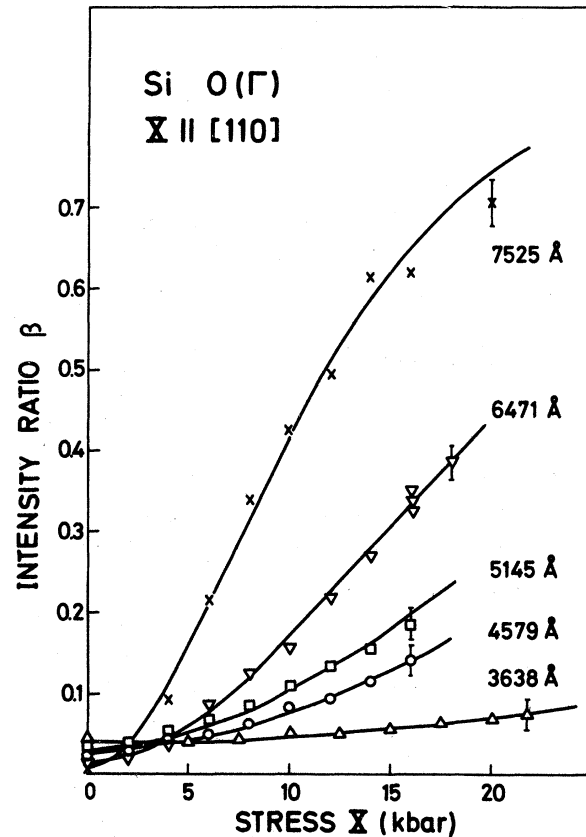


FIG. 2. Intensity ratio β vs stress X for the zone-center optical phonon under $[110]$ stress [case (a)]. The experimental results for five different exciting wavelengths (marked in the figure) are fit using Eq. (4). The best fits obtained are indicated by the solid lines.

TABLE II. Magnitudes of the piezo-optical constants obtained for different exciting frequencies. The signs of $\pi_{11} - \pi_{12}$ and π_{44} can be inferred to be negative from comparison with long-wavelength data from Ref. 1. The superscripts a-f refer to the various scattering geometries given in Table I.

Exciting wavelength (Å)	$\pi_{11} - \pi_{12}$ (10^{-14} cm ² /dyn)	π_{44} (10^{-14} cm ² /dyn)	$\frac{1}{2}(\pi_{11} - \pi_{12} + \pi_{44})$ (10^{-14} cm ² /dyn)
3638		32.3 ± 5.5 ^a	
4579	5.9 ± 0.7 ^b	10.5 ± 0.7 ^a	
5145	8.1 ± 0.7 ^b	8.6 ± 0.5 ^a	
6471	9.3 ± 0.6 ^b	6.9 ± 0.5 ^a	8.8 ± 0.5 ^f
		7.5 ± 0.5 ^c	
		7.7 ± 0.5 ^d	
7525		7.25 ± 0.3 ^a	

Case (b). Stress $\bar{X} \parallel [001]$, (100) face: The second-order acoustical phonon 2TA(X) at a frequency of approximately 300 cm⁻¹ has mainly $\Gamma_1 (A_{1g})$ symmetry. It has zero intensity (Table I) in the $z(xy)\bar{z}$ configuration and a nonzero intensity in the $z(xx)\bar{z}$ configuration, where x and y are defined in Table I. Hence $\beta = I_{xy}/I_{xx}$, and the stress dependence is given by

$$\beta = \frac{I_{xy}}{I_{xx}} = \frac{1}{1 + 1/2(BX)^2}, \quad (5a)$$

where

$$B = \pi n_0^3 (\pi_{11} - \pi_{12}) / \lambda (\alpha_i + \alpha_s). \quad (5b)$$

The piezo-optical coefficient $\pi_{11} - \pi_{12}$ obtained in this configuration is related to $n_{\parallel} - n_{\perp}$ through¹⁰

$$n_{\parallel} - n_{\perp} = -\frac{1}{2} n_0^3 (\pi_{11} - \pi_{12}) X. \quad (5c)$$

The same functional form for β is found as for the optical phonon in case (a); in Fig. 3 we plot β vs X in this configuration for different exciting frequencies. The solid lines are fits to the experimental points using Eq. (5a). The uncertainties in these fits are somewhat larger than for the O(Γ) optical phonon since the 2TA(X) mode is weaker than the optical phonon. The intensities I_{xx} and I_{xy} were obtained by tuning the monochromator to the peak of the 2TA(X) structure and counting the number of scattered photons in a 5-min interval. Contrary to the case of the O(Γ) optical phonon, it was not necessary to scan the monochromator or to retune it after stress was applied because of the small shift of the 2TA(X) structure with stress (approximately 0.15 cm⁻¹/kbar of uniaxial stress¹²) as compared with its large linewidth. Since good resolution was not required, wide slits were used to eliminate any errors introduced by not scanning the monochromator. Values of $\pi_{11} - \pi_{12}$ obtained in this configuration are listed in Table II. Two of the wavelengths used for the optical phonon, 7525 and 3638

Å, could not be conveniently used for the 2TA(X) owing to the lower available laser power (150 mW as against 500 mW for the 4579, 5145, and 6471 Å lines) and consequent low signal for 2TA(X) scattering.

The two cases discussed above are sufficient to obtain $\pi_{11} - \pi_{12}$ and π_{44} . The following four cases were measured for a single wavelength (6471 Å) in order to check the self-consistency of the analysis of the experimental data.

Case (c). Stress $\bar{X} \parallel [111]$, (1 $\bar{1}0$) face. The zone-

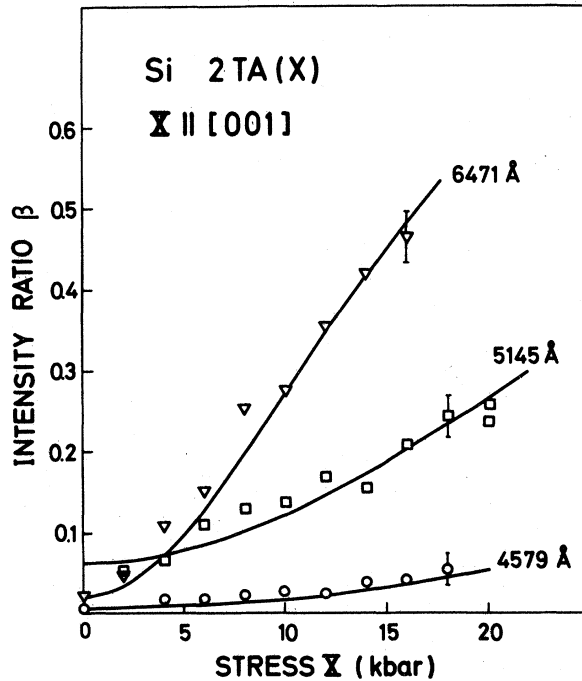


FIG. 3. Intensity ratio β vs stress X for the second-order acoustical phonon 2TA(X) under [100] uniaxial stress. The experimental data for three exciting wavelengths are fit using Eq. (5) (solid lines).

center optical phonon has zero intensity in the $z(x'y')\bar{z}$ configuration and a nonzero intensity in the $z(x'y)\bar{z}$ configuration (Table I), where x' is $[001]$ and y' is $[110]$.

The electric vectors given in Eq. (1) are easily rewritten to account for the fact that the polarizations are not at 45° to the stress: since the $[11\bar{2}]$ direction is at 90° to both the normal to the scattering face and the stress direction,

$$\begin{aligned} \hat{e}_{x'} &= \frac{1}{3} ([111] - [11\bar{2}]e^{i\phi}), \\ \hat{e}_{y'} &= \frac{1}{3\sqrt{2}} (2[111] + [11\bar{2}]e^{i\phi}). \end{aligned} \quad (6)$$

$I_{x'x'}$, and $I_{x'y'}$, are defined in a manner similar to Eq. (3). β is obtained to be

$$\beta = \frac{I_{x'y'}}{I_{x'x'}} = \frac{16(AX)^2[1+2(AX)^2]}{9+33(AX)^2+20(AX)^4} \quad (7)$$

and A is defined in Eq. (4b). In Fig. (4a) we plot β vs X in this configuration for an exciting wavelength of 6471 \AA . The fit (solid line) to Eq. (7) gives the parameter A and therefore π_{44} , which is found, within experimental error, to be the same

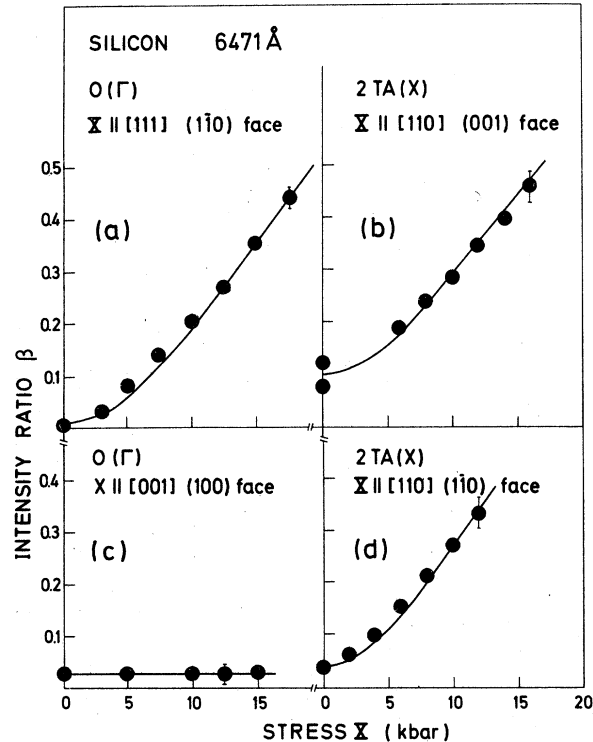


FIG. 4. Intensity ratios β vs stress X for an exciting wavelength of 6471 \AA . The filled circles are experimental points. The solid lines are fits using the appropriate expressions given in the text: (a) represents case (c), (b) represents case (d), (c) represents case (e), and (d) represents case (f) (Table I).

as that obtained in case (a) (Table II).

Case (d). Stress $\bar{X} \parallel [110]$, (001) face: the second order acoustical phonon $2TA(X)$ was used to obtain π_{44} in a manner similar to case (a). $\beta = I_{xy}/I_{xx}$ and is given as a function of stress by

$$\beta = \frac{I_{xy}}{I_{xx}} = \frac{1}{1+1/2(AX)^2}, \quad (8)$$

a functional form identical to Eq. (4a) in case (a).

The experimental data obtained and the fit to Eq. (8) are shown in Fig. (4b). The value of β at zero stress is seen to be quite large ($\approx 10\%$) in this configuration. This is explained by the fact that a small component ($\approx 5\% - 10\%$) of the intensity of the $2TA(X)$ scattering appears in $\Gamma_{25'}$, symmetry,¹³ while the rest appears in Γ_1 symmetry. At zero stress the component of $\Gamma_{25'}$ symmetry is allowed in the (xy) configuration, while that of Γ_1 symmetry appears in the (xx) configuration (Table I) so that at zero stress β is not zero but the ratio of the intensities of the $\Gamma_{25'}$, and Γ_1 components of the $2TA(X)$ (plus the leakage). Since the $\Gamma_{25'}$ component of the $2TA(X)$ is small, we neglect any changes due to stress, and fit the experimental data with Eq. (8) by shifting the zero on the β axis as in the other cases. The value of π_{44} obtained is in agreement with cases (a) and (c) within experimental error (Table II).

Case (e). Stress $\bar{X} \parallel [001]$, (100) face. The optical phonon $O(\Gamma)$ is observed (Table I) in the $z(xx)\bar{z}$ configuration but not in the $z(xy)\bar{z}$ configuration. Equations (3) yield for this case

$$\beta = \frac{I_{xy}}{I_{xx}} = 0 \quad (9)$$

as a function of stress. The experimental intensity ratio shown in Fig. (4c) also remains unchanged under stress and is equal to the leakage at zero stress. This configuration provides a useful check on our theoretical analysis of intensity ratios.

Case (f). Stress $\bar{X} \parallel [110]$, $(1\bar{1}0)$ face. The major (Γ_1) component of the $2TA(X)$ scattering has non-zero intensity in the $z(xx)\bar{z}$ configuration and zero intensity in the $z(xy)\bar{z}$ configuration (Table I). β as a function of stress is

$$\beta = \frac{I_{xy}}{I_{xx}} = \frac{1}{1+1/2(CX)^2}, \quad (10a)$$

where

$$C = \pi n_0^3 (\pi_{11} - \pi_{12} + \pi_{44}) / 2\lambda (\alpha_i + \alpha_s). \quad (10b)$$

Figure 4(d) shows experimental data and the fit to Eq. (10a), from which we obtain $\frac{1}{2}(\pi_{11} - \pi_{12} + \pi_{44})$. The result agrees with values obtained for $\pi_{11} - \pi_{12}$ and π_{44} using cases (a)–(d) for the same exciting wavelength of 6471 \AA (Table II). We note

again that the experiments yield only the absolute value of the corresponding piezo-optical coefficients. Their sign must be determined by extrapolation to long wavelengths and comparison with the sign obtained in the classical stress-induced birefringence measurements performed in the region of transparency.¹ Equation (10b), however, enables us to determine the relative sign of $\pi_{11} - \pi_{12}$ and π_{44} once their magnitudes have been found from the other experimental configurations: they are found to have the same sign (Table II), in agreement with the negative signs found for both piezo-optical constants at long wavelengths¹ (Sec. IV).

The values of $\pi_{11} - \pi_{12}$ and π_{44} obtained from these experiments are summarized in Table II. A wide spectrum of available laser lines, from 7525 to 3638 Å, were used. The values of the average refractive index n_0 and the absorption coefficient $\frac{1}{2}(\alpha_i + \alpha_s)$ (averaged between incident and scattered frequencies for both 2TA(X) and O(Γ) phonons¹⁴) are listed in Table III. In Fig. 5 we plot the values obtained for the piezo-optical constants $\pi_{11} - \pi_{12}$ (triangles) and π_{44} (circles) as a function of energy. In the figure we include the piezo-optical constants obtained from the data of Higginbotham *et al.*¹ in the energy region below 1.2 eV. The solid lines are theoretical fits to be discussed in Sec. IV.

In calculating the contribution to the stress-induced birefringence from microscopic theory, one obtains directly the difference between the dielectric constants parallel and perpendicular to the stress direction $\epsilon_{\parallel} - \epsilon_{\perp}$, which is related to

the quantity $n_{\parallel} - n_{\perp}$ in Eq. (2) through the standard relation

$$\epsilon = n^2. \quad (11a)$$

We neglect the imaginary parts of the dielectric constant and the refractive index, which should be a fairly good approximation below the E'_0 and $E_1, E_1 + \Delta_1$ gaps (below 3.3 eV). Then

$$\epsilon_{\parallel} - \epsilon_{\perp} = 2n_0(n_{\parallel} - n_{\perp}). \quad (11b)$$

A piezo-optical constant, for example π_{44} , is then related to $\epsilon_{\parallel} - \epsilon_{\perp}$ by [Eq. (4c)]

$$\pi_{44} = -\frac{1}{n_0^4} \left(\frac{\epsilon_{\parallel} - \epsilon_{\perp}}{X} \right) \bar{\chi}_{\parallel[111]} \quad (11c)$$

$\pi_{11} - \pi_{12}$ is related in a similar manner to $(\epsilon_{\parallel} - \epsilon_{\perp})/X$ for a stress parallel to [001].

In order to directly compare experiment with theory we plot in Fig. 6 the experimental values of $(\epsilon_{\parallel} - \epsilon_{\perp})/X$ for stress $\bar{X} \parallel [001]$ (triangles) obtained from our data in case (b) (Fig. 3) and from Ref. 1 for the energy range from 0.6 to 1.2 eV. For stress $\bar{X} \parallel [110]$ $(\epsilon_{\parallel} - \epsilon_{\perp})/X$ is plotted in Fig. 7 (circles) using data from case (a) (Fig. 2) and the data between 0.6 and 1.2 eV for stress $\bar{X} \parallel [111]$ in Ref. 1. (The piezo-optical coefficient obtained is π_{44} in both cases.) The solid lines in Figs. 6 and 7 are theoretical fits and the squares are scaled values from piezoreflectance data; both will be discussed in Sec. IV.

IV. THEORY AND DISCUSSION

The band structure of silicon is well known from a variety of calculations and experiments.¹⁵⁻¹⁷

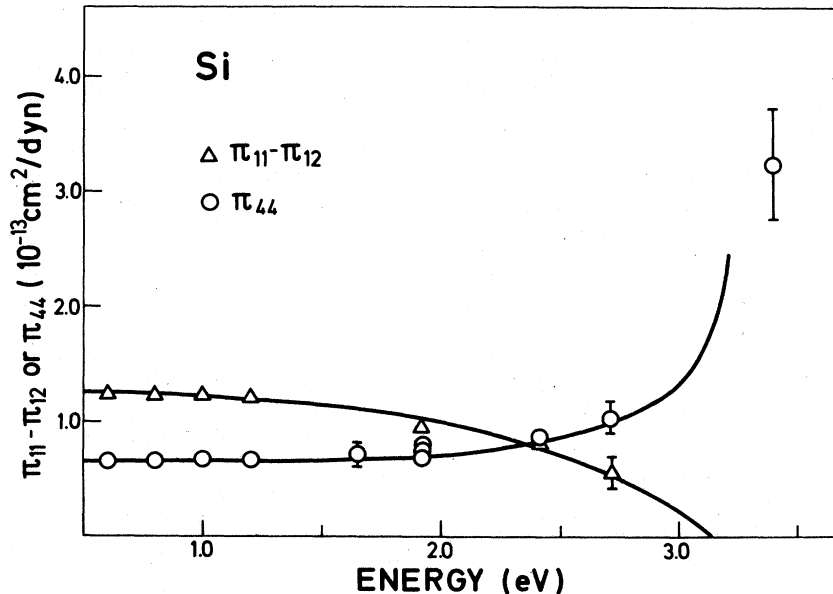


FIG. 5. Experimentally obtained values of the piezo-optical constants $\pi_{11} - \pi_{12}$ (triangles) and π_{44} (circles) as a function of energy. The data below 1.5 eV are obtained from Ref. 1 and those above 1.5 eV from present investigations. The solid lines are theoretically calculated values obtained from the best fits to $(\epsilon_{\parallel} - \epsilon_{\perp})/X$ in Figs. 6 and 7.

TABLE III. Values of the refractive index n_0 and absorption coefficient $\frac{1}{2}(\alpha_i + \alpha_s)$ (averaged between incident and scattered frequencies) used for the optical phonon and the second-order acoustic phonon in calculating $\pi_{11} - \pi_{12}$ and π_{44} (from Ref. 14).

Exciting wavelength (Å)	O(Γ)		2 TA(X)	
	n_0	$\frac{1}{2}(\alpha_i + \alpha_s)$ (cm ⁻¹)	n_0	$\frac{1}{2}(\alpha_i + \alpha_s)$ (cm ⁻¹)
3638	6.75	6.36×10^5		
4579	4.51	2.14×10^4	4.53	2.21×10^4
5145	4.17	9.75×10^3	4.18	1.0×10^4
6471	3.83	3.01×10^3	3.82	3.09×10^3
7525	3.70	1.28×10^3		

The lowest direct transitions occur at an energy of about 3.3 eV. The major contribution to the dielectric constant arises from the E_1 , $E_1 + \Delta_1$ transitions along the $\langle 111 \rangle$ directions, and a contribution with low oscillator strength E'_0 arises from transitions at the center of the Brillouin zone. The next direct gap E_2 is at approximately 4.4 eV. Not many details are known about this gap; the corresponding transitions are believed to spread over a large region around the X point in the Brillouin zone. We calculate contributions to piezobirefringence from the E_1 , $E_1 + \Delta_1$ and E_2 transitions, neglecting the E'_0 gap due to its low oscillator strength. The E_1 , $E_1 + \Delta_1$ transitions provide a strong dispersive term close to 3.3 eV, while the E_2 gap provides a background term in

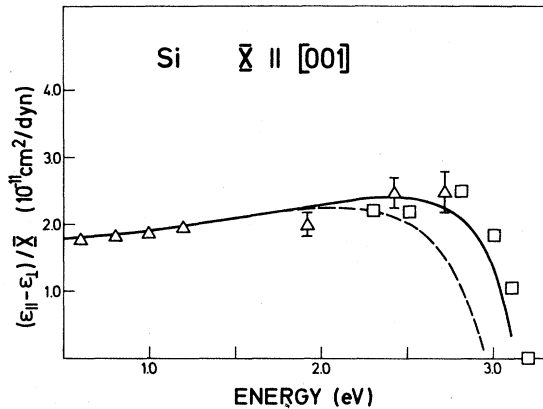


FIG. 6. $(\epsilon_{\parallel} - \epsilon_{\perp})/X$ as a function of energy for stress along $[001]$. The experimental data (triangles) were obtained from Ref. 1 (below 1.5 eV) and present measurements (above 1.5 eV). The solid line is the best fit using Eq. (20), obtained with $D_3^2 = -1.8$ eV and $C_2 = 2.27 \times 10^{-11}$ cm²/dyn. The dashed line, which coincides with the solid line at low energies is obtained for $D_3^2 = -4$ eV and $C_2 = 2.8 \times 10^{11}$ cm²/dyn. The squares are scaled values obtained from Ref. 7.

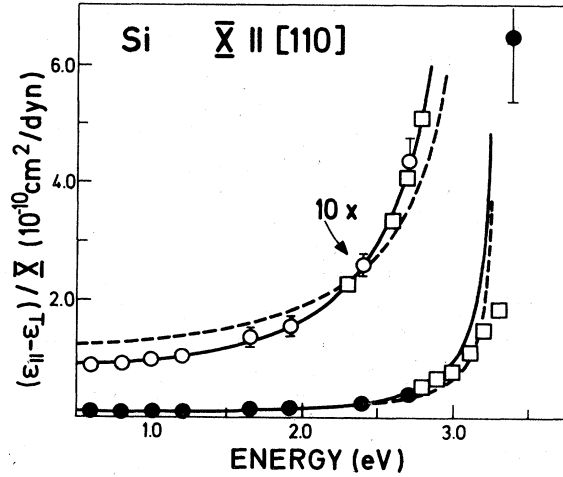


FIG. 7. $(\epsilon_{\parallel} - \epsilon_{\perp})/X$ as a function of energy for stress along $[110]$. The experimental data (circles) were obtained from Ref. 1 (below 1.5 eV) and present experiments (above 1.5 eV). The filled circles are plotted on the scale indicated in the figure, while the open circles are replots of the same values on an expanded ($10 \times$) scale. The squares are scaled values obtained from Ref. 5. The solid lines are the fits using Eq. (21), corresponding to $D_1^5 + 2\sqrt{2}D_3^5 = 40.6$ eV and $C_2^5 = -1.3 \times 10^{-11}$ cm²/dyn. The dashed lines are obtained for $D_1^5 + 2\sqrt{2}D_3^5 = 22.3$ eV and $C_2^5 = 0$.

the energy region studied in our experiments (1.65–3.4 eV).

A. Contribution from the $E_1, E_1 + \Delta_1$ gaps

The $E_1, E_1 + \Delta_1$ transitions arise from critical points along all the equivalent $\langle 111 \rangle$ directions.¹⁸ The contribution to the real part of the dielectric constant from the E_1 critical points can be written as^{1,19}

$$\epsilon_1(\omega) - 1 = \frac{-B}{\pi} |\langle |p| \rangle|^2 \frac{1}{\omega_1^2} \left(\frac{1}{x_1^2} \ln(1 = x_1^2) \right), \quad (12a)$$

where

$$B = \frac{4\sqrt{3} \pi m^*}{a_0} \quad (12b)$$

(in atomic units). In Eq. (12b) m^* is the effective mass perpendicular to the $[111]$ direction and a_0 the lattice constant, $|\langle |p| \rangle|^2$ is the square of the transition matrix element between valence and conduction bands, ω_1 the energy of the E_1 transition, and $x_1 = \omega/\omega_1$. A similar expression can be written for the $E_1 + \Delta_1$ transition substituting $\omega_{1s} = \omega_1 + \Delta_1$ for ω_1 and $x_{1s} = \omega/\omega_{1s}$ for x_1 .

The birefringence induced in the material upon

the application of a uniaxial stress is discussed in Ref. 19. Two types of contributions have to be considered: those arising from stress induced changes in matrix elements and those due to the splitting of the various equivalent $\langle 111 \rangle$ gaps induced by the stress. Stress-induced changes in m^* are neglected because they give a less dispersive contribution to the piezobirefringence than the changes in gap and matrix element. For the purpose of a fit to the experimental data this contribution can be considered to be included in the weakly dispersive contribution due to the E_2 gap to be discussed later. For a [100] stress the $\langle 111 \rangle$ gaps remain equivalent. Thus only changes in matrix elements due to a stress-induced coupling between the spin-orbit split valence bands contribute to the piezobirefringence. Following Ref. 19 we find

$$\left(\frac{\epsilon_{\parallel} - \epsilon_{\perp}}{X} \right)_{E_1, E_1 + \Delta_1}^{[001]} = + \frac{16\sqrt{2}}{3} \frac{D_3^3(S_{11} - S_{12})}{a_0 \Delta_1 \omega_1} \times \left[-\frac{1}{x_1^2} \ln(1 - x_1^2) + \left(\frac{\omega_1}{\omega_{1s}} \right) \frac{1}{x_{1s}^2} \ln(1 - x_{1s}^2) \right]. \quad (13)$$

Equation (13) is identical to Eq. (91') of Ref. 19 except for the correction of two misprints and for having expressed $\delta\omega_1$ in terms of the deformation potential D_3^5 as given in Ref. 20,

$$\delta\omega_1 = (2\sqrt{2}/\sqrt{3}) D_3^5 (S_{11} - S_{12}) X. \quad (14)$$

For a [111] stress both energy splittings of the $\langle 111 \rangle$ gaps and matrix element changes contribute to the piezobirefringence. The net effect is given by [see Eq. (96) of Ref. 19]

$$\left(\frac{\epsilon_{\parallel} - \epsilon_{\perp}}{X} \right)_{E_1, E_1 + \Delta_1}^{[111]} = \frac{16\sqrt{2}}{9} \frac{S_{44} D_3^5}{a_0 \omega_1 \Delta_1} \left[-\frac{1}{x_1^2} \ln(1 - x_1^2) + \left(\frac{\omega_1}{\omega_{1s}} \right) \frac{1}{x_{1s}^2} \ln(1 - x_{1s}^2) \right] + \frac{8}{9} \frac{D_1^5 S_{44}}{a_0 \omega_1^2} \left[\frac{1}{1 - x_1^2} + \left(\frac{\omega_1}{\omega_{1s}} \right)^2 \frac{1}{1 - x_{1s}^2} \right]. \quad (15)$$

Throughout this work the *compressive* stresses applied in our experiments are assumed to be *negative*. The first term in the right-hand side of Eq. (15), analogous to Eq. (13), is due to changes in matrix elements produced by the stress-induced intravalence band splitting $\delta\omega_1$ of Ref. 19 expressed in terms of the deformation potential²⁰ D_3^5

$$\delta\omega_1 = \frac{1}{2} \frac{\sqrt{2}}{\sqrt{3}} D_3^5 S_{44} X. \quad (16)$$

The second term on the right-hand side of Eq. (15) represents the effect of the stress-induced splittings of the $\langle 111 \rangle$ gaps. The deformation potential \mathcal{E}_2 of Ref. 19 has been expressed in terms of D_1^5 of Ref. 20.

$$\mathcal{E}_2 = (\sqrt{3}/2) D_1^5. \quad (17)$$

Although the second term in Eq. (15) is in principle more dispersive than the first one, in the limit of small spin-orbit splitting (a condition that holds in silicon since $\Delta_1 = 0.04$ eV and $\omega_1 = 3.3$ eV) the difference between the logarithmic terms also tends to a singularity of the type $(1 - x_1^2)^{-1}$, plus another less dispersive term. We shall assume that these less dispersive terms are included in the contribution due to the E_2 gap and in this approximation we can write

$$\left(\frac{\epsilon_{\parallel} - \epsilon_{\perp}}{X} \right)_{E_1, E_1 + \Delta_1}^{[111]} = \frac{8}{9} \frac{S_{44}}{a_0 \omega_1^2} (D_1^5 + 2\sqrt{2} D_3^5) \times \left[\frac{1}{1 - x_1^2} + \left(\frac{\omega_1}{\omega_{1s}} \right)^2 \frac{1}{1 - x_{1s}^2} \right]. \quad (18)$$

It is obvious from this expression that no infor-

mation on the relative magnitudes of D_1^5 and D_3^5 can be obtained from a fit to the experimental results.

B. Contribution from the E_2 gap

Owing to lack of information on the nature of the E_2 gap, contributions to piezobirefringence are approximated by a constant¹⁹ or a harmonic oscillator dispersion.¹ We use the harmonic oscillator approximation to fit our data; however, the difference between using a harmonic oscillator and a constant is not found to be critical since the energy region of interest is sufficiently far from this gap, which is at 4.4 eV. The contribution to piezobirefringence from this gap is written as¹

$$[(\epsilon_{\parallel} - \epsilon_{\perp})/X]_{E_2} \sim 1 + 2x_2^2, \quad (19)$$

where $x_2 = \omega/\omega_2$, and ω_2 is the energy of the E_2 gap. Equation (19) was derived under the assumption of an effect due only to stress induced changes in the gap. If the effect is due mainly to changes in matrix elements, the factor of 2 in front of the x_2^2 term Eq. (19) would have to be removed. We have tried to use this factor as a fitting parameter without any significant improvement in the fits to experimental data. We therefore use a factor of 2 throughout the discussion.

The total contribution from both E_1 , $E_1 + \Delta_1$ and E_2 gaps for [001] stress therefore is

$$\begin{aligned} \left(\frac{\epsilon_{\parallel} - \epsilon_{\perp}}{X} \right)^{[001]} &= + \frac{16\sqrt{2}}{3} \frac{D_3^3(S_{11} - S_{12})}{a_0 \Delta_1 \omega_1} \\ &\times \left[-\frac{1}{x_1^2} \ln(1 - x_1^2) \right. \\ &\quad \left. + \left(\frac{\omega_1}{\omega_{1s}} \right) \frac{1}{x_{1s}^2} \ln(1 - x_{1s}^2) \right] \\ &+ C_2(1 + 2x_2^2) \end{aligned} \quad (20)$$

and for [111] stress

$$\begin{aligned} \left(\frac{\epsilon_{\parallel} - \epsilon_{\perp}}{X} \right)^{[111]} &= \frac{8}{9} \frac{S_{44}}{a_0 \omega_1^2} (D_1^5 + 2\sqrt{2} D_3^5) \\ &\times \left[\frac{1}{1 - x_1^2} + \left(\frac{\omega_1}{\omega_{1s}} \right)^2 \frac{1}{1 - x_{1s}^2} \right] \\ &+ C_2'(1 + 2x_2^2). \end{aligned} \quad (21)$$

In Fig. 6 we plot the experimental points (triangles) obtained for $(\epsilon_{\parallel} - \epsilon_{\perp})/X$ with $\vec{X} \parallel [001]$. The points above 1.5 eV were obtained in this work and those below 1.5 eV from Ref. 1. Using Eq. (20), $\omega_1 = 3.3$ eV, $\omega_{1s} = 3.344$ eV, and $\omega_2 = 4.4$ eV, and using the elastic compliance constants of Ref. 21, we obtained the best fit for $D_3^3 = -1.8$ eV and $C_2 = 2.27 \times 10^{-11}$ cm²/dyn (solid line). Previous measurements of D_3^3 indicate a value close to -4 eV.^{18,22} For comparison, we plot the fit obtained for this value of D_3^3 with $C_2 = 2.8 \times 10^{-11}$ cm²/dyn (Fig. 6, dashed lines). We also plot in Fig. 6 $(\epsilon_{\parallel} - \epsilon_{\perp})/X$ obtained from the Kramers-Kronig analysis⁵ of the data of Ref. 4 (squares). Since only relative values as a function of energy are obtained in the work of Ref. 4 we have scaled the results to compare them with ours. The agreement between this data (after scaling), our experimental values and the fit for $D_3^3 = -1.8$ eV is good, particularly around the energy at which $(\epsilon_{\parallel} - \epsilon_{\perp})/X$ drops to zero (antiresonance), which is independent of the scaling of the results of Refs. 4 and 5.

In Fig. 7 we plot $(\epsilon_{\parallel} - \epsilon_{\perp})/X$ versus energy for [110] stress and a (001) scattering face. The circles indicate experimental points, those below 1.5 eV obtained from Ref. 1 and those above 1.5 eV from present experiments. (The filled circles are plotted on the scale marked in figure, the open circles on a 10 \times expanded scale.) The best fit of Eq. (21) to experiment, using C_2' and $D_1^5 + 2\sqrt{2} D_3^5$ as adjustable parameters is indicated by the solid line, obtained for $C_2' = -1.3 \times 10^{-11}$ cm²/dyn and $D_1^5 + 2\sqrt{2} D_3^5 = 40.6$ eV. The transition energies used were $\omega_1 = 3.3$ eV, $\omega_{1s} = 3.344$ eV, and $\omega_2 = 4.4$ eV. Though the fit is very good, the deformation potential $D_1^5 + 2\sqrt{2} D_3^5$ needed is about a factor of 2 larger than previously measured values.^{18,22} Using the most favorable values

from Ref. 18, $D_1^5 + 2\sqrt{2} D_3^5 = 22.3$ eV, (corresponding to $D_1^5 = 11$ eV and $D_3^5 = 4$ eV) we plot in Fig. 7 $(\epsilon_{\parallel} - \epsilon_{\perp})/X$ from Eq. (21) for $C_2' = 0$ (dashed lines). Agreement with experiment is seen to be worse. We also plot in Fig. 7 the scaled values obtained from Kramers-Kronig analysis of piezo-reflectance data^{4,5} (squares); they agree quite well with present experiments and the solid-line fit, as was the case for a [001] stress. The highest experimental point was obtained with our technique at $\omega = 3.38$ eV for a [110] stress, as indicated in Fig. 7. Due to the lack of points at intermediate frequencies we are not able to infer the sign of the effect at $\omega = 3.38$ eV. The theory is not expected to be sufficiently accurate at this frequency. In the frequency region close to the gap real transitions occur and the exact linewidth (not only the form of the singularity), including the imaginary part of the stress induced dielectric constant, is required for an accurate description. A second complication arises from the fact that the energy of the E_1 gap increases under uniaxial stress so that the energies of the incident and scattered light lie in the region of a singularity that is shifting as stress is applied. In fact, we observed a resonance enhancement of the intensity of the phonon as the gap reached the energy of the scattered radiation. As such, the measurement of π_{44} at this energy is representative only of the approximate magnitude, and indicates the limit at which the present method can be used to measure the piezo-optical constants in silicon. The large experimental error in the result at 3.38 eV arises from the small change in the intensity ratio β (Fig. 2) as a function of stress, which in turn is due to the small penetration depth.

As already mentioned, discrepancies of factors of 2 appear between previous determinations of D_3^3 and $D_1^5 + 2\sqrt{2} D_3^5$ and the present values obtained from our fits to $\pi_{11} - \pi_{12}$ and π_{44} . The previously determined values are higher than the present one for D_3^3 and lower for $D_1^5 + 2\sqrt{2} D_3^5$. This fact excludes the possibility of correcting the discrepancy by changing the oscillator strength of the E_1 transitions [Eqs. (12)]. The discrepancy may lie in the simplicity of our model, but it should also be noted that experimental determinations differ considerably among themselves.²² Previous values were determined by tracking the frequency dependence of a rather broad reflectivity peak which may not adequately represent the critical energy E_1 which enters into Eqs. (12).

While our measurements alone do not allow us to determine the sign of $(\epsilon_{\parallel} - \epsilon_{\perp})/X$ and therefore those of the piezo-optical constants or deformation potentials, by extrapolating our results to long wavelengths so that they are compatible with

those of Higginbotham *et al.*,¹ we obtain $\epsilon_{\parallel} - \epsilon_{\perp}$ to be negative for compressive stresses (X negative) along [001] and [111] at energies far from the gap, so that the piezo-optical constants $\pi_{11} - \pi_{12}$ and π_{44} are negative [Eq. (11c)] in this region. Upon approaching the E_1 gap, $(\epsilon_{\parallel} - \epsilon_{\perp})/X$ for [001] stress (Fig. 6) approaches zero close to 3 eV and is expected to change sign and become negative [Eq. (20)] between 3 eV and the energy of the E_1 gap: in this region the dominant term in Eq. (20) is the one that contains D_3^3 , so we conclude that D_3^3 is negative. By a similar argument, for $\bar{X} \parallel [111]$, $(\epsilon_{\parallel} - \epsilon_{\perp})/X$ remains positive from low energies up to the region below the E_1 gap (Fig. 7), so that $D_1^5 + 2\sqrt{2} D_3^5$ is positive. In order to obtain the best possible agreement between previous determinations of the deformation potentials²² and the present ones, we conclude that both D_1^5 and D_3^5 must have the same sign, i.e., positive. Earlier work^{18,22} yielded only the magnitudes of D_3^5 and D_3^3 but not their signs. The sign of D_1^5 can, however, be inferred from Refs. 18 and 22 to be positive as well. A positive sign for D_1^5 has also been found for Ge, GaAs,²³ GaSb, and InSb.²⁴

V. CONCLUSIONS

Two combinations of piezo-optical constants of silicon have been measured as a function of pho-

ton energy in the region 1.65–3.4 eV where the material is opaque. A technique based on the depolarization of Raman structures upon application of uniaxial stress was used. We found the magnitude of the piezo-optical constant $\pi_{11} - \pi_{12}$ to decrease with increasing frequency reversing sign (antiresonance) at about 3.0 eV, while that of π_{44} was found to increase strongly without reversing sign. This dispersion of piezobirefringence was fitted with a theory based on a two-dimensional critical point model of the E_1 gap.

From this fit the sign and magnitude of three deformation potentials related to the E_1 gap were determined. They agree to within a factor of 2 with determinations based on different experimental techniques.

Note added in proof. Contrary to the statements made in the text, it has been found that the sign of the elasto-optical constants can be determined by inserting a Babinet compensator in the incident beam and determining if it enhances or decreases the observed depolarization of the scattered light. If the fast and slow axes of the compensator are known, the sign of the π_{ij} can be deduced.

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